

=> d his

(FILE 'HOME' ENTERED AT 13:32:38 ON 27 MAY 2005)

FILE 'REGISTRY' ENTERED AT 13:33:00 ON 27 MAY 2005

L1 SCREEN 964 AND 1015
L2 STRUCTURE UPLOADED
L3 QUE L2 AND L1
L4 0 S L3 SSS SAM

FILE 'HCAPLUS, CAPLUS, USPATFULL' ENTERED AT 13:33:32 ON 27 MAY 2005

L5 0 S L4

FILE 'HOME' ENTERED AT 13:34:20 ON 27 MAY 2005

FILE 'REGISTRY' ENTERED AT 13:34:58 ON 27 MAY 2005

L6 SCREEN 964 AND 1015
L7 STRUCTURE UPLOADED
L8 QUE L7 AND L6
L9 0 S L8 SSS SAM

FILE 'HCAPLUS, CAPLUS, USPATFULL' ENTERED AT 13:35:19 ON 27 MAY 2005

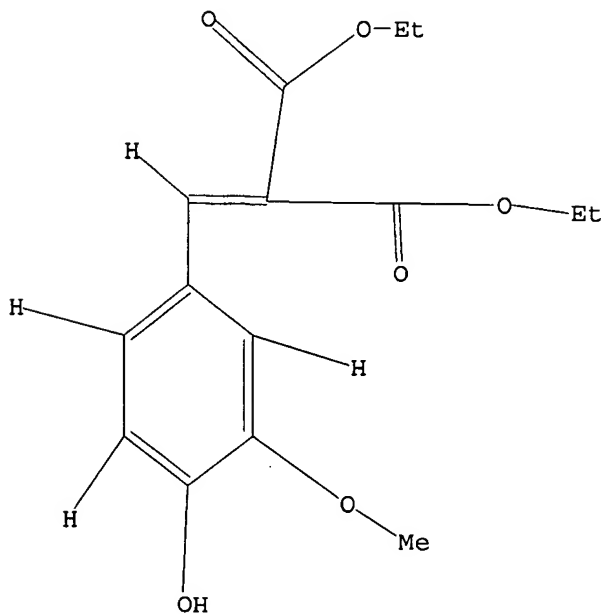
L10 0 S L9

FILE 'REGISTRY' ENTERED AT 13:35:36 ON 27 MAY 2005

=> d 18

L8 HAS NO ANSWERS

L6 SCR 964 AND 1015
L7 STR



Structure attributes must be viewed using STN Express query preparation.

L8 QUE ABB=ON PLU=ON L7 AND L6

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	644699	resin photoresist resist	USPAT	OR	ON	2005/05/27 13:41
L2	623396	positive	USPAT	OR	ON	2005/05/27 13:41
L3	13524	quencher (basic adj compound)	USPAT	OR	ON	2005/05/27 13:41
L4	6768	((photoacid acid) adj generator) (photoactive adj component)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/05/27 13:46
L5	50690	(light radiation uv ultraviolet molar) adj (absorber absorbance)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/05/27 14:04
L6	46	1 and 2 and 3 and 4 and 5	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/05/27 14:45
L7	1656	((light radiation uv ultraviolet molar) adj (absorber absorbance)) same styrene	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/05/27 14:04
L8	8	6 and 7	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/05/27 14:32
L9	2	jp-2000194127-\$.did.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/05/27 14:44
L10	1	jp-2005049810-\$.did.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/05/27 14:44
L11	38	6 not (8 9 10)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/05/27 14:46
L12	2330	absorber same (styrene)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/05/27 15:04
L13	3324	absorber same (aromatic)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/05/27 15:04
L14	11	13 and 1 and 2 and 4 and 5	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/05/27 15:30

L15	4	((("5362598") or ("20020006574")).PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2005/05/27 15:30
L16	11	("4135007" "4349619" "4645735" "4882260" "4927732").PN. OR ("5362598").URPN.	US-PGPUB; USPAT; USOCR	OR	ON	2005/05/27 15:34
L17	39	("3970639" "4013806" "4019972" "4039720" "4349619" "4431726" "4443534" "4464462" "4575480" "4626492" "4762767").PN. OR ("4135007" "4645735" "4927732").URPN.	US-PGPUB; USPAT; USOCR	OR	ON	2005/05/27 15:52
L18	3912	(photoacid acid) adj generator	US-PGPUB; USPAT; USOCR	OR	ON	2005/05/27 15:52
L19	464307	(resist photoresist)	US-PGPUB; USPAT; USOCR	OR	ON	2005/05/27 15:52
L20	24234	(uv ultraviolet) adj absorber	US-PGPUB; USPAT; USOCR	OR	ON	2005/05/27 15:53
L21	113	18 and 19 and 20	US-PGPUB; USPAT; USOCR	OR	ON	2005/05/27 15:53
L22	730974	resin (alkali adj soluble)	US-PGPUB; USPAT; USOCR	OR	ON	2005/05/27 15:54
L23	111	21 and 22	US-PGPUB; USPAT; USOCR	OR	ON	2005/05/27 15:53
L24	8297	(alkali adj soluble)	US-PGPUB; USPAT; USOCR	OR	ON	2005/05/27 15:54
L25	67	24 and 21	US-PGPUB; USPAT; USOCR	OR	ON	2005/05/27 15:54
S1	4	((("5362598") or ("20020006574")).PN.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2004/09/28 19:07
S2	0	("2002/0006574").URPN.	USPAT	OR	ON	2004/09/28 19:22
S3	5	("4135007" "4349619" "4645735" "4882260" "4927732").PN.	US-PGPUB; USPAT; USOCR	OR	ON	2004/09/28 19:22
S4	6	("5362598").URPN.	USPAT	OR	ON	2004/09/28 19:39
S5	23117	thioxanthone ((light uv ultraviolet) adj absorber)	USPAT	OR	ON	2004/09/28 19:44
S6	1293	radiation adj absorber	USPAT	OR	ON	2004/09/28 19:42
S7	2191	((photoacid acid) adj generator) (photoactive adj component)	USPAT	OR	ON	2004/09/28 19:43
S8	622131	resin photoresist resist	USPAT	OR	ON	2005/05/27 13:41
S9	603231	positive	USPAT	OR	ON	2005/05/27 13:41
S10	24162	S5 S6	USPAT	OR	ON	2004/09/28 19:41
S11	203	S10 and S7 and S8 and S9	USPAT	OR	ON	2004/09/28 19:42
S12	12927	quencher (basic adj compound)	USPAT	OR	ON	2005/05/27 13:41
S13	47	S11 and S12	USPAT	OR	ON	2004/09/28 19:42
S14	2172	radiation adj absorber	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/05/27 13:48

S15	5914	((photoacid acid) adj generator) (photoactive adj component)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2004/09/30 12:33
S16	42091	thioxanthone ((light uv ultraviolet) adj absorber)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2004/09/30 12:32
S17	2466952	resin photoresist resist	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2004/09/28 19:43
S18	1344723	positive	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2004/09/28 19:43
S19	29127	quencher (basic adj compound)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2004/09/30 12:34
S20	82	(S16 S14) and S15 and S17 and S18 and S19	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2004/09/29 17:30
S21	3041	(molar adj extinction adj coefficient) (molar adj absorbance)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2004/09/29 17:30
S22	2172	radiation adj absorber	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2004/09/29 17:30
S23	5914	((photoacid acid) adj generator) (photoactive adj component)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2004/09/29 17:30
S24	42091	thioxanthone ((light uv ultraviolet) adj absorber)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2004/09/30 13:50
S25	2466952	resin photoresist resist	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2004/09/29 17:30
S26	1344723	positive	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2004/09/29 17:30
S27	29127	quencher (basic adj compound)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2004/09/29 17:30

S28	82	(S24 S22) and S23 and S25 and S26 and S27	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2004/09/29 17:33
S29	8	S21 and S28	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2004/09/29 17:33
S30	2773	molar adj extinction adj coefficient	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/09/30 12:32
S31	77646	(light uv ultraviolet) adj (absorption absorber)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2004/09/30 12:33
S32	647	S30 and S31	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2004/09/30 12:33
S33	5932	((photoacid acid) adj generator) (photoactive adj component)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/05/27 13:42
S34	622131	resin photoresist resist	USPAT	OR	ON	2004/09/30 12:33
S35	29179	quencher (basic adj compound)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2004/09/30 12:34
S36	1	S32 and S33 and S34 and S35	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2004/09/30 12:35
S37	6466	\$20thioxanthone thioxanth\$3one	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2004/09/30 13:50
S38	18895	\$20benzylidene benzylidene\$10	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/09/30 13:51
S39	9579	(S37 S38) and absorb\$4	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/09/30 13:57
S40	1259	(S37 S38) same absorb\$4	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/09/30 13:57
S41	4	S33 and S40 and S34 and S35	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/09/30 13:57

S42	2951	(S37 S38) same (absorb\$4 sensitizer additive)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/09/30 13:57
S43	33	S33 and S42 and S34 and S35	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/09/30 13:58
S44	33	S41 S43	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/09/30 13:58